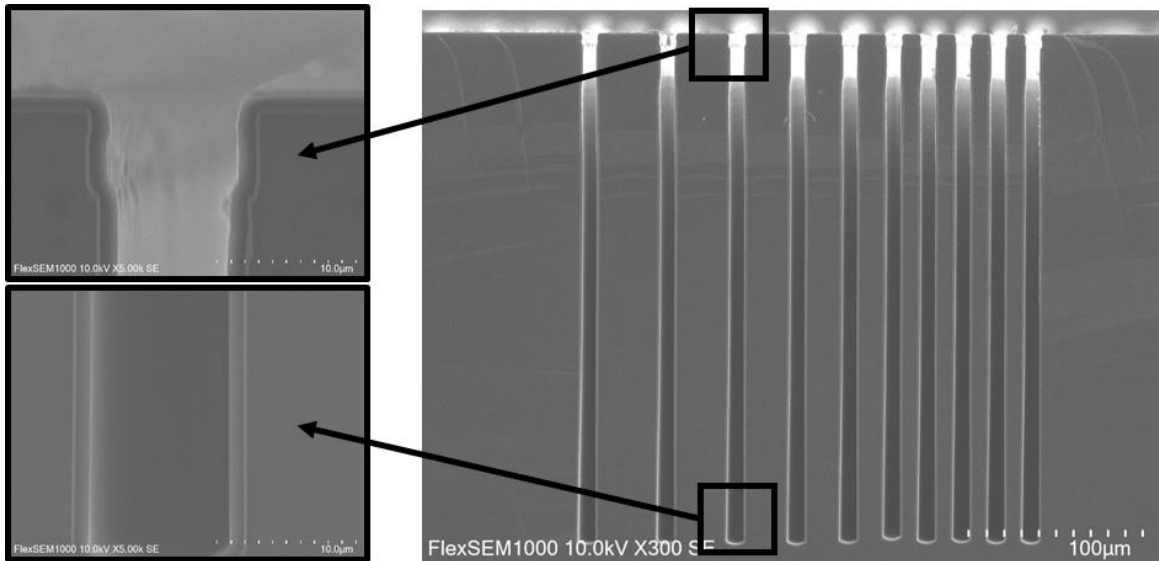


~ 400 nm  $\text{SiO}_2$  deposited at 180 cycles per minute on trench with overhanging aperture. ~500 nm of  $\text{Ta}_2\text{O}_5$  was previously deposited using conventional pulsed ALD, to provide image contrast and narrow aperture.



$1.2\mu$   $\text{SiO}_2$  deposited at 120 cycles per minute on trenches with  $10\mu$  width and  $300\mu$  depth. ~150 nm of  $\text{Ta}_2\text{O}_5$  was previously deposited using conventional pulsed ALD to provide image contrast.